

Philippe Rodriguez is research engineer and head of the Advanced Materials Deposition Laboratory at the CEA-Leti in the Semiconductor Platform Division.

He received his PhD in 2007 from Lyon 1 University in materials chemistry for his work on metalorganic vapor phase epitaxy growth of B(In)GaAs epilayers. From 2007 to 2009, he worked for the CNRS (French National Center for Scientific Research) and developed coating methods on structured supports for process intensification applications. In 2009, he started his career at the CEA (French Alternative Energies and Atomic Energy Commission). First, he worked on the coating and fluidization of dense powder by fluidized bed metalorganic chemical vapor deposition for the development of new nuclear fuels (2009 – 2011). Then, he developed silica permeation barriers by magnetron sputtering for Laser Megajoule gaseous targets (2011 – 2013). Finally, he joined the CEA-Leti institute in Oct. 2013. His research activity is mainly focused on advanced contact technologies for electronics and photonics applications. He develops contact metallization for advanced CMOS and photonics devices (Si, Ge(Sn), III-V and GaN materials) and also deals with the surface preparation and interface modulation prior to metallization. He led the CEA-Leti’s Contact Team between 2017 and 2020 and became head of the Advanced Materials Deposition Laboratory in Feb. 2020.

He is the author and co-author of about 85 articles in peer reviewed journals, 100 international conference papers, 2 book chapters and 10 patents.